

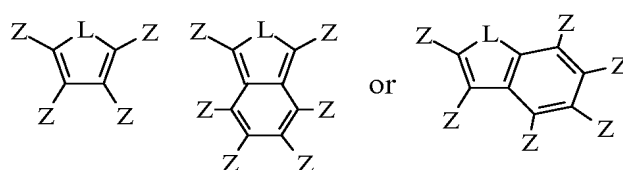
Amendment to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

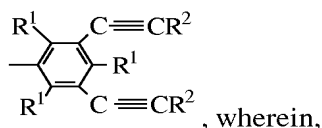
1-10. canceled

11. (currently amended) A monomer ~~according to claim 1~~ corresponding to the formula:



wherein L is -O-, -S-, -N=N-, -(CO)-, -(SO₂)-, or -O(CO)- ;

Z is independently in each occurrence hydrogen, halogen, an unsubstituted or inertly substituted aromatic group, an unsubstituted or inertly substituted alkyl group, or two adjacent Z groups together with the carbons to which they are attached form a fused aromatic ring, and in one occurrence, Z is

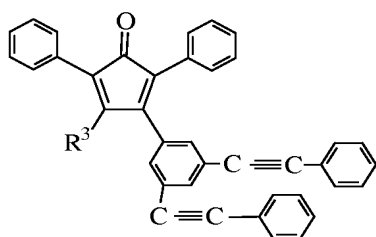


R¹ is independently each occurrence selected from the group consisting of hydrogen, halo, C₁₋₄ alkyl, C₆₋₆₀ aryl, and C₇₋₆₀ inertly substituted aryl groups; and

R² is independently each occurrence selected from the group consisting of hydrogen, C₁₋₄ alkyl, C₆₋₆₀ aryl, and C₇₋₆₀ inertly substituted aryl groups.

12. (previously presented) A monomer according to claim **11** which is a 2- or 3-di(arylethynyl)aryl-substituted cyclopentadienone compound.

13. (previously presented) A monomer according to claim **12** represented by the formula:



wherein R3 is C₆₋₂₀ aryl or inertly substituted aryl.

14. (previously presented) A monomer according to claim **13** where in R3 is phenyl, biphenyl, p-phenoxyphenyl or naphthyl.

15. (previously presented) A monomer comprising a single aromatic ring that has two acetylenic groups attached to it, and said single aromatic ring being directly, covalently attached to a 2,4-cyclopentadienone or benz-2,4-cyclopentadienone ring structure, characterized in that the cyclopentadienone of one monomer is capable of reacting under cycloaddition reaction conditions with an acetylene group of a second monomer, thereby resulting in formation of an aromatic ring.

16. (currently amended) A spin-coatable, curable composition comprising a monomer according to claim 11~~10~~, an optional solvent, and an optional pore forming material.

17. (previously presented) A spin-coatable, curable composition comprising a monomer according to claim 15, an optional solvent, and an optional pore forming material.

18. (previously presented) A method of forming an insulating film on an electrical device comprising coating the device with a composition according to claim **16**, removing the optional solvent, curing the monomer, and optionally removing the optional pore forming material.

19. (previously presented) A method of forming an insulating film on an electrical device comprising coating the device with a composition according to claim **17**,

removing the optional solvent, curing the monomer, and optionally removing the optional pore forming material.

20. (previously presented) An electrical device comprising an insulating film prepared according to claim 18.

21. (previously presented) An electrical device comprising an insulating film prepared according to claim 19.